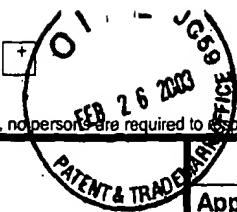


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PTO/SB/08A (08-00)

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Substitute for form 1449B/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	09/698,317
				Filing Date	October 27, 2000
				First Named Inventor	Choi et al.
				Group Art Unit	2859
				Examiner Name	Unassigned <i>T. Dougherty</i>
Sheet	2	of	2	Attorney Docket Number	PA09-06V02

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cita No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²	
<i>TMD</i>	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.		
<i>TMD</i>	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291.		
<i>TMD</i>	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).		
<i>TMD</i>	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.		
<i>TMD</i>	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.		
<i>TMD</i>	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.		

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Examiner Signature	<i>Thomas M. Dougherty</i>	Date Considered	2-12-04
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¹Unique citation designation number. ²Applicant is to place a check mark here if English language Translation is attached.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 2 of 2

Applicati n Number	09/698,317
Filing Dat	October 27, 2000
First Nam d Inv nt r	Choi et al.
Group Art Unit	2834
Examiner Name	Dougherty, Thomas M.
Attorney Docket Number	UTS-09-06V02

[illegible]

Thomas M. Ruppel

Feb. 12, 2004

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Form PTO-1449 (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
tmj	A1	3,807,027	4/1974	Heisler	29	423	
tmj	A2	3,807,029	4/1974	Troeger	29	436	
tmj	A3	3,811,665	5/1974	Seelig	26	RECEIVED	
tmj	A4	4,062,600	12/1977	Wyse	384	285	2002
tmj	A5	4,098,001	7/1978	Watson	33	644	
tmj	A6	4,155,169	5/1979	Drake et al.	33	GROUP 3600	
tmj	A7	4,202,107	5/1980	Watson	33	644	
tmj	A8	4,267,212	5/1981	Sakawaki	427	240	
tmj	A9	4,337,579	7/1982	De Fazio	33	644	
tmj	A10	4,355,469	10/1982	Nevins et al.	267	150	
tmj	A11	4,414,750	11/1983	De Fazio	267	166	
tmj	A12	4,451,507	5/1984	Beltz et al.	427	240	
tmj	A13	4,610,442	9/1986	Oku et al.	269	73	
tmj	A14	4,694,703	11/1987	Routson	79	5F	
tmj	A15	4,731,155	3/1988	Napoli et al.	216	44	
tmj	A16	4,763,886	8/1988	Takei	269	73	
tmj	A17	4,929,083	5/1990	Brunner	356	400	
tmj	A18	4,959,252	11/1990	Bonnebat et al.	428	64.7	
tmj	A19	5,072,126	12/1991	Progler	250	548	
tmj	A20	5,110,514	5/1992	Soane	264	496	
tmj	A21	5,126,006	6/1992	Cronin et al.	438	702	
tmj	A22	5,204,739	4/1993	Domenicali	348	79	
tmj	A23	5,240,550	8/1993	Boehnke et al.	216	24	
tmj	A24	5,348,616	9/1994	Hartman et al.	216	48	
tmj	A25	5,392,123	2/1995	Marcus et al.	356	625	
tmj	A26	5,425,964	6/1995	Southwell et al.	427	10	
tmj	A27	5,452,090	9/1995	Progler et al.	356	401	

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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>DMB</i>	A28	5,480,047	1/1996	Tanigawa et al.	216	12	
<i>DMB</i>	A29	5,512,131	4/1996	Kumar et al.	438	355	
<i>DMB</i>	A30	5,515,167	5/1996	Ledger et al.	356	595	
<i>DMB</i>	A31	5,545,367	10/1996	Bae et al.	264	401	
<i>DMB</i>	A32	5,566,584	10/1996	Briganti et al.	74	490.01	
<i>DMB</i>	A33	5,633,505	5/1997	Chung et al.	250	491.1	
<i>DMB</i>	A34	5,724,145	3/1998	Kondo et al.	356	632	
<i>DMB</i>	A35	5,753,014	5/1998	Van Rijn	96	12	
<i>DMB</i>	A36	5,760,500	6/1998	Kondo et al.	310	12	
<i>DMB</i>	A37	5,772,905	6/1998	Chou	216	44	
<i>DMB</i>	A38	5,776,748	7/1998	Singhvi et al.	435	180	
<i>DMB</i>	A39	5,779,799	7/1998	Davis	118	663	
<i>DMB</i>	A40	5,802,914	9/1998	Fassler et al.	74	110	
<i>DMB</i>	A41	5,877,036	3/1999	Kawai	438	16	
<i>DMB</i>	A42	5,877,861	3/1999	Ausschnitt et al.	356	401	
<i>DMB</i>	A43	5,888,650	3/1999	Calhoun et al.	428	354	
<i>DMB</i>	A44	5,900,160	5/1999	Whitesides et al.	216	41	
<i>DMB</i>	A45	5,912,049	6/1999	Shirley	427	240	
<i>DMB</i>	A46	5,942,871	8/1999	Lee	318	611	
<i>DMB</i>	A47	5,948,470	9/1999	Harrison et al.	427	198	
<i>DMB</i>	A48	5,952,127	9/1999	Yamanaka	430	5	
<i>DMB</i>	A49	6,038,280	3/2000	Rossiger et al.	378	50	
<i>DMB</i>	A50	6,039,897	3/2000	Lochhead et al.	264	1,24	
<i>DMB</i>	A51	6,046,056	4/2000	Parce et al.	204	403.05	
<i>DMB</i>	A52	6,051,345	4/2000	Huang	430	5	
<i>DMB</i>	A53	6,074,827	6/2000	Nelson et al.	435	6	
<i>DMB</i>	A54	6,091,485	7/2000	Li et al.	356	73	
	A55	6,128,085	10/2000	Buermann et al.	356	369	

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Form PTO-1449 (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

U.S. PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JMD	A56	6,143,412	11/2000	Schueller et al.	428	408	
JMD	A57	6,168,845	1/2001	Fontana, Jr. et al.	428	65.5	
JMD	A58	6,180,239	1/2001	Whitesides et al.	428	411.1	
JMD	A59	6,204,922	3/2001	Chalmers	356		
JMD	A60	6,334,960	1/2002	Wilson et al.	216	52	

FOREIGN PATENT DOCUMENTS

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
JMD	A61	00/54107	9/2000	WO	608F	7/00	
JMD	A62	01/33232	5/2001	WO	601R	—	
JMD	A63	01/33300	5/2001	WO	402K	5/24	
JMD	A64	244884	3/1987	EP	829C	33/34	
JMD	A65	733455	9/1996	EP	829C	33/34	NO
JMD	A66	2800476	7/1978	DE	603C	5/08	NO
JMD	A67	19648844	11/1999	DE	829C	59/02	NO
JMD	A68	1-196749	8/1989	JP	611B	7/26	NO

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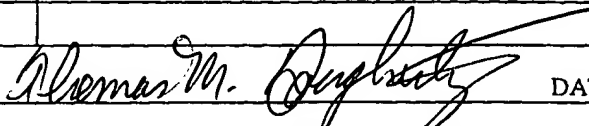
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Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SER. NO. 09/698,317 RECEIVED GROUP 2859 JUN 26 2002 GROUP 3600
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)			
<i>fmb</i>	A69	Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378.	
<i>fmb</i>	A70	Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156.	
<i>fmb</i>	A71	Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133.	
<i>fmb</i>	A72	Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7.	
<i>fmb</i>	A73	Hollis, Ralph; Salcudean, S.E.; Allan, A.P.; "A Six-Degree-of-Freedom Magnetically Levitated Variable Compliance Fine-Motion Wrist: Design, Modeling and Control", IEEE Transactions on Robotics and Automation, 1991, 7, 320-332.	
<i>fmb</i>	A74	Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", Journal of Japan Society of Precision Engineering, 1992, 118-124.	
<i>fmb</i>	A75	Slocum, Alexander; "Precision Machine Design: Macromachine Design Philosophy and its Applicability to the Design of Micromachines", Proc. of IEEE Micro Electro Mech. Systems Workshop, 1992, 37-42.	
<i>fmb</i>	A76	Krug, Herbert; Merl, Norbert; Schmidt, Helmut; "Fine Patterning of Thin Sol-Gel Films", Journal of Non-Crystalline Solids, 1992, 447-450.	
<i>fmb</i>	A77	Arai, T.; Larssonneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of IECON, 1993, 1660-1665.	
<i>fmb</i>	A78	Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", IEEE Transactions on Robotics and Automation, 1993, 9, 831-837.	
<i>fmb</i>	A79	Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-Positioning Stages", ASME, 1994, 2, 979-985.	
<i>fmb</i>	A80	Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE International Conference on Robotics and Automation, 1994, 2457-2462.	
<i>fmb</i>	A81	Merlet, J.P.; "Parallel Manipulators: State of the Art and Perspectives", Advanced Robotics, 1994, 8, 589-596.	
<i>fmb</i>	A82	Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, 1994, 2, 677-686.	
<i>fmb</i>	A83	Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T.; "Development of a New Parallel Manipulator with Fixed Linear Actuator", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149.	
<i>fmb</i>	A84	Howell, L.L.; Midha, A.; "Loop-Closure Theory of the Analysis and Synthesis of Compliant Mechanisms", Journal of Mechanical Design, 1996, 118, 121-125.	
<i>fmb</i>	A85	Haisma, J. et al.; "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication", Journal of Vacuum Science and Technology, 1996, 14, 4124-4128.	
<i>fmb</i>	A86	Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in Microrobotics", Robotica, 1997, 15, 417-420.	

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Feb. 13, 2004

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Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859
tmj	A87	Rong, L.; Guang, L.; "Dynamics of Parallel Mechanism with Direct Compliance Control", IEEE, 1997, 1753-1758.	
tmj	A88	Mittal, Samir; Menq, Chia-Hsiang; "Precision Motion Control of Magnetic Suspension Actuator Using a Robust Nonlinear Compensation Scheme", IEEE/ASME Transactions on Mechatronics, 1997, 2, 268-280.	
tmj	A89	Physik Instruments, Product Catalog for Micropositioning, 1997.	
tmj	A90	Williams, Mark et al.; "Six Degree of Freedom Mag-Lev Stage Development", SPIE, 1997, 3051, 856-867.	
tmj	A91	Lee, Chang-Woo; Kim, Seung-Woo; "Ultraprecision Stage for Alignment of Wafers in Advanced Microlithography", Precision Engineering, 1997, 21, 113-122.	
tmj	A92	Kanetomo, M.; Kashima, H.; Suzuki, T.; "Robot for Use in Ultrahigh Vacuum", Solid State Tech., 1997, 63-72.	
tmj	A93	Goldfarb, M.; Speich, J.; "Compliant Micromanipulator Design for Scaled Bilateral Telemanipulation of Small-Scale Environments", ASME, Dynamic Systems and Control Div., 1998, 64, 213-218.	
tmj	A94	Koseki, Y. et al.; "Design and Accuracy Evaluation of High-Speed and High Precision Parallel Mechanism", Proc. of IEEE, Intl. Conf. on Robotics & Automation, 1998, 1340-1345.	
tmj	A95	Kim, Won-Jong; Trumper, David; "High Precision Magnetic Levitation Stage for Photolithography", Precision Engineering, 1998, 22, 66-77.	
tmj	A96	Mansky, P. et al.; "Large-Area Domain Alignment in Block Copolymer Thin Films Using Electric Fields", Macromolecules, 1998, 31, 4399-4401.	
tmj	A97	Wang, W.; Loh, R.; Gu, E.; "Passive Compliance Versus Active Compliance in Robot-Based Automated Assembly Systems", Industrial Robot, 1998, 25, 48-57.	
tmj	A98	Scheer, H.C. et al.; "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition", Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.	
tmj	A99	Xia, Y.; Whitesides, George; "Soft Lithography", Annu. Rev. Mater. Sci., 1998, 28, 153-184.	
tmj	A100	Tajbakhsh, H. et al.; "Three-Degree-of-Freedom Optic Mount for Extreme Ultraviolet Lithography", ASPE, 1998, 18, 359-362.	
tmj	A101	Lee, Dong Sung et al.; "Ultra Precision Positioning System for Servo Motor-Piezo Actuator Using Dual Servo Loop and Digital Filter Implementation", ASPE, 1998, 18, 287-290.	
tmj	A102	Wu, Wei et al.; "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography", 1998, Journal of Vacuum Science and Technology, 1998, 16, 3825-3829.	
tmj	A103	Ohya, Y. et al.; "Development of 3-DOF Finger Module for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 894-899.	
tmj	A104	Tanikawa, T. et al.; "Development of Small-Sized 3 DOF Finger Module in Micro Hand for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 876-881.	
tmj	A105	Colburn, M. et al.; "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, 3676, 379-389.	

EXAMINER:

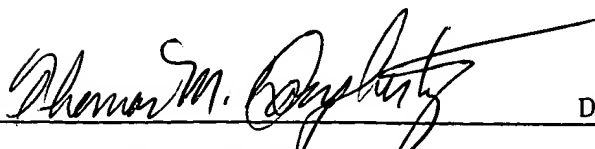
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Information Disclosure Statement--PTO 1449 (modified)

Form PTO-1449 (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		PAT. & TRADEMARK OFFICE JUN 21 2002	PATTY. DKT. NO. 5119-0860 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859 JUN 26 2002 GROUP 3600
DMB	A106	Lucas Aerospace, Free-Flex Pivot Catalog, 1999		
DMB	A107	Goldfarb, M.; Speich, J.E.; "A Well-Behaved Revolute Flexure Joint for Compliant Mechanism Design", Journal of Mech. Design, 1999, 121, 424-429.		
DMB	A108	Geodetic Technology, G1000-PS Power Series Specifications, 1999, from www.hexapods.com		
DMB	A109	Hexel Corporation, Tornado 2000 System Specifications, 1999, from www.hexel.com		
DMB	A110	Physik Instruments, PI Online-Catalog, 1999, from www.physikinstrument.com		
DMB	A111	Chou, Stephen; Zhuang, Lei; "Lithographically-induced Self Assembly of Periodic Micropillar Arrays", Journal of Vacuum Science and Technology, 1999, 17, 3197-3202.		
DMB	A112	Ruchhoeft, P. et al.; "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography", Journal of Vacuum Science and Technology, 1999, 17, 2965-2982.		
DMB	A113	Vanderbilt University Office of Transfer Technology; VU 9730 Specifications for Improved Flexure Device; 2001, from www.vanderbilt.edu		
DMB	A114	Stix, Gary; "Getting More from Moore's", Scientific American, 2001, from www.scientificamerican.com		
DMB	A115	Trilogy Systems, Linear Motors 310 Specification, 2001, from www.trilogysystems.com		
DMB	A116	Choi, B.J. et al.; "Design of Orientation Stages for Step and Flash Imprint Lithography", Precision Engineering, 2001, 25, 192-199.		
DMB	A117	PCT International Search Report for PCT/US 00/30041, dated 10/15/2001		
DMB	A118	PCT International Search Report for PCT/US 01/26049, dated 2/19/2002		

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Information Disclosure Statement--PTO 1449 (modified)